

UV and DUV Exposure Sources



Abet Technologies Model 12008 1W 6 x 6 DUV Exposure Source

Innovative, Integrated and Adaptable

The Abet Gen II optical design, shared with all the solar simulators on the preceding pages, dramatically increases the percentage of photons reaching the work plane. All components are integrated in a single housing. 4x4 and 6x6 inch illuminated fields are most popular, other field sizes are available.

Dichroic reflectors are available to narrow down the spectral range. Additional spectral shaping can be achieved with filters, e.g. Model 12075 T-Topping for SU-8 resist, frequently used for MEMS generation.

Ordering Information

A small sampling of Abet UV and DUV exposure systems and accessories. Please contact Abet with your UV source and mask alignment requirements.

- 12002 200 W Hg Source, 4x4 in, 350-450
- 12008 1 kW DUV HgXe source, 6x6 in
- 12075 T-Topping filter for SU-8

- Gen II Optics for High Efficiency Illumination
- Hg and HgXe 200 W to 1 kW Lamps
- +/- 5% Uniformity
- Long Life Shutter Included
- Digital Shutter Timer Included
- HEPA Filtered Cooling
- Ozone venting attachment for DUV

Specifications

Irradiance uniformity..... +/-5% or better
 Electronic shutter (long life)included
 Electronic shutter timerincluded
 Elapsed Time Meterincluded
 Working Distance..... 8 in/200 mm (typical)
 Universal Input 90-250V, 50-60Hz, power supply included
 Standard Output Direction.....Down
Horizontal output optional
 HEPA filtered cooling fan.....included
 Below are typical output powers in the 350 to 450 nm spectra region for two different wattage sources. Information on other spectral regions is available on request.

Work Plane Size	200 Hg Watt Systems	500 Hg Systems
2 x 2 Inch	378mW cm ²	865mW cm ²
4 x 4 Inch	94mW cm ²	215mW cm ²
6 x 6 Inch	42mW cm ²	97mW cm ²
8 x 8 Inch	23mW cm ²	52mW cm ²

Abet Technologies regularly continues to upgrade our products, therefore all specifications are subject to change without notice.



Abet Technologies Model 12002 200 W Hg source with a mask aligner for SU-8 based MEMS.